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Applicant(s): Yoshinori NISHIWAKI et al.			2002JP314D
Serial No. 10/532,364	Filing Date April 20,2005	Examiner To Be Assigned	Group Art Unit To Be Assigned
Invention: CHEMICALLY AMPLIFIED POSITIVE PHOTSENSITIVE RESIN COMPOSITION			
<div data-bbox="142 457 376 676"></div> <p>I hereby certify that this <u>English Language abstract of JP 62-124556 - 2 Pages</u> <i>(Identify type of correspondence)</i></p> <p>is being deposited with the United States Postal Service as first class mail in an envelope addressed to: The Commissioner of Patents and Trademarks, Washington, D.C. 20231-0001 on <u>September 21, 2005</u> <i>(Date)</i></p> <p><u>MARIA T. SANCHEZ</u> <i>(Typed or Printed Name of Person Mailing Correspondence)</i></p> <p><u></u> <i>(Signature of Person Mailing Correspondence)</i></p> <p>Note: Each paper must have its own certificate of mailing.</p>			

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(54) PHOTSENSITIVE COMPOSITION AND PHOTSENSITIVE LITHOGRAPHIC PLATE MATERIAL

(57)Abstract:

PURPOSE: To obtain a photosensitive composition high in photosensitivity, wide in processing allowance at the time of development, and superior in resistance to processing chemicals by using a novolak type resin containing at least 3 different kinds of phenols only in combination with a positive type photosensitive material composed of a compound capable of generating acid on irradiation of actinic rays and an acid-decomposable type compound.

CONSTITUTION: The photosensitive resin composition contains the compound capable of generating acid on irradiation of actinic rays and a compound having at least one acid-decomposable bond, and the novolak type resin containing at least 3 different kinds of phenols. As the acid-decomposable compound, ones such as having an acetal or ketal group, or polymers each having an orthocarboxylic ester group on the principal chain, are used, preferably, in a amount of 5W70wt% of the total solid of the photosensitive resist-forming composition. As the novolak resin, polycondensed novolak resins containing at least 3 kinds of phenols are preferably used.

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